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	US Dept. of Com TRADE ATENT & TRADEMARK O FORMATION DISCLOSURE STATEMENT	ATTY DOCKET NO. 106452			APPLICATION NO. 10/046,245			
(Use several sheets if necessary)			APPLICANT(S) Cathie J. BURKE et al.					
				FILING DATE GRO January 16, 2002 1756				
U.S. PATENT DOCUMENTS								
EXAMINER INITIAL	DOCUMENT NUMBER		DATE	NAME		CLASS	SUB CLASS	
DV)	5,344,748	9/19	994	Feely			330	
M	5,738,799	4/19	998	Hawkins et al.			27	
DVD	5,485,181	1/19	996	Convers			63	
MUP	5,699,094	12/1	1997	Burke et al.			63	
FOREIGN PATENT DOCUMENTS								
	DOCUMENT NUMBER	I	DATE	COUNTRY		CLASS	SUB CLASS	
							·	
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)								
ND	S. Hagan et al., "Photosensitive Polyimide: Lithography in the Thick-Film Regime," Proceedings 11th International Conference Photopolymers Principles, Processes, and Materials, Society of Plastics Engineers, Inc., Oct. 6-8, 1997, p. 422 437							
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Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

Date: April 9, 2002